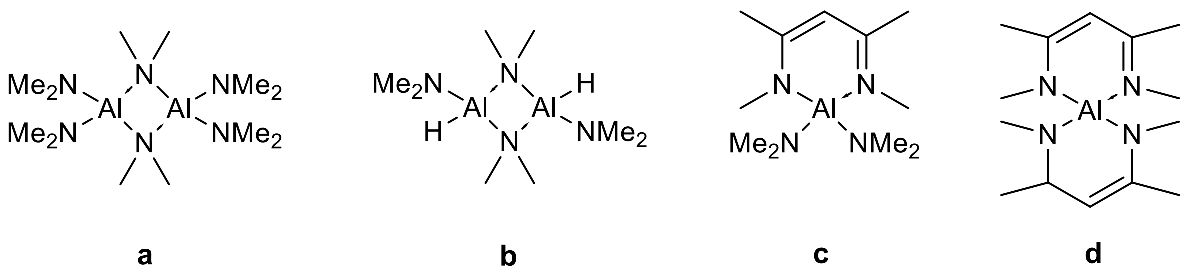

Figure 1: a) Tris(dimethylamido)aluminum(III), b) $AlH(NMe_2)_2$, c) $Al(^{Me}NacNac)(NMe_2)_2$ and d) $Al(^{Me}NacNac)(^{r,Me}NacNac)$ as simple precursors for AlN deposition.